

T4. Emerging Technologies for Advanced Optical Lithography

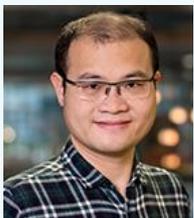
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TOPICS

- Extreme Ultraviolet (EUV) Lithography
- Emerging Techniques for EUV/DUV Source
- Computational Lithography
- Metrology and Process Control
- Next-Generation Lithography Materials
- Optics for EUV/DUV Lithography

Important Dates

Submission Deadline July 15, 2025	Notification Date August 15, 2025	Registration Deadline August 31, 2025
Camera-ready Papers Due August 31, 2025	On-site Sign in Date September 09, 2025	Main Conference Dates September 09-12, 2025

Publication & Submission

- After a rigorous peer-review process, all accepted papers after proper registration and presentation, will be submitted for inclusion into IEEE Xplore subject to meeting IEEE Xplore's scope and quality requirements.
- Please send your manuscript to EasyChair online submission system: <https://easychair.org/conferences/?conf=ogc2025>

